Amendments to the Claims

1 – 13. Cancelled

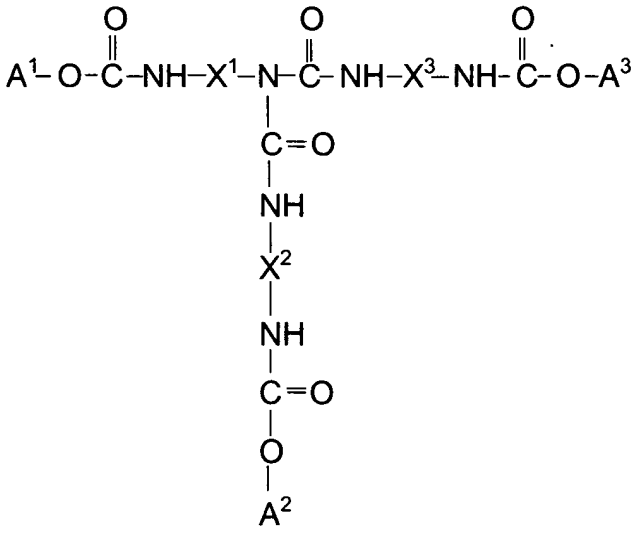
14 (New). A radiation-sensitive element comprising

(a) an optionally pretreated substrate;

(b) a radiation-sensitive coating comprising

(i) at least one photoinitiator or sensitizer, which is capable of absorbing radiation of a wavelength in the range of 250 to 1,200 nm;

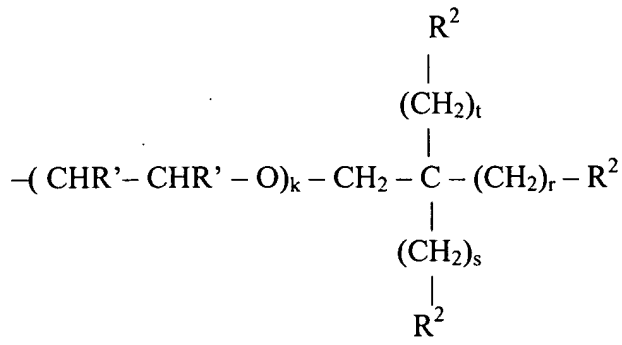
(ii) at least one oligomer A of formula (I)



(I)

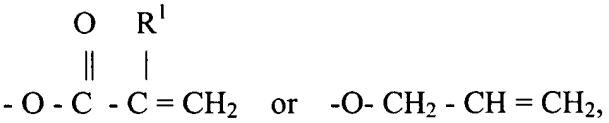
wherein X^1, X^2 and X^3 are independently $C_2 - C_{18}$ alkanediyl or $C_6 - C_{20}$ arylene,
A^1, A^2 and A^3 are independently

$-(CHR'-CHR'-O)_k - CH_2 - CH = CH_2$ or a fragment represented by formula Ia



(Ia)

wherein k is an integer from 0 to 10, each R' is independently a hydrogen atom or CH_3, each R^2 is independently a hydrogen atom,

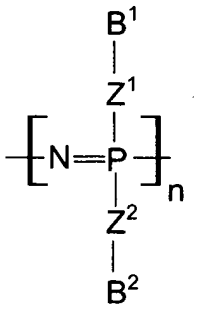


R^1 is a hydrogen atom or $C_1 - C_{12}$ alkyl and

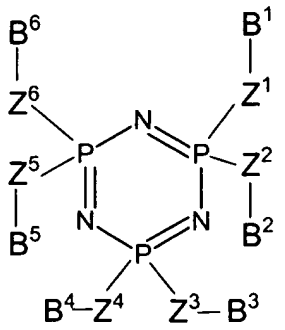
r, s and t independently are 0 or 1,

with the proviso that in each fragment A^1, A^2 and A^3 at least one R^2 is not a hydrogen atom if A^1, A^2 and A^3 are all a fragment represented by formula (Ia), and

(iii) at least one oligomer B, which is a phosphazene, represented by formulas (II) or (IIa):

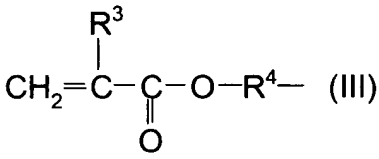


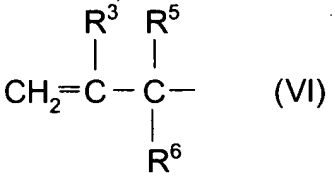
(II)



(IIa)

wherein Z^1, Z^2, Z^3, Z^4, Z^5 and Z^6 are independently –O– or –NR–, R is a hydrogen atom or $C_1 - C_{12}$ alkyl, n is greater than 3 and B^1, B^2, B^3, B^4, B^5 and B^6 are fragments represented by formulas (III) – (VIII)


(III)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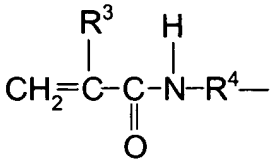
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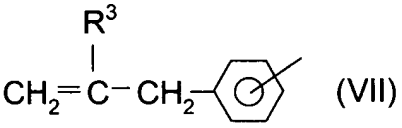
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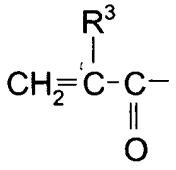
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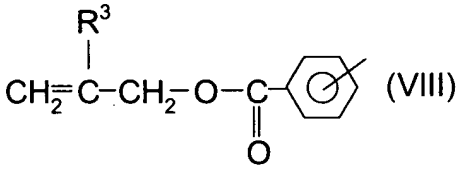

(VIII)

wherein R^3 is a hydrogen atom or $C_1 - C_{12}$ alkyl, R^4 is $C_2 - C_{12}$ alkanediyl and R^5 and R^6 are independently a hydrogen atom or $C_1 - C_{12}$ alkyl; and

(c) optionally, at least one additive comprising coinitiators which form free radicals after the excitation of the initiator or sensitizer with radiation of a wavelength of 250 to 1,200 nm, binders, thermopolymerization inhibitors, dyes, plasticizers, chain transfer agents, leuco dyes, inorganic fillers or surfactants.

15 (New). The radiation-sensitive element according to claim 14, wherein X^1, X^2 and X^3 are the same in oligomer A.

16 (New). The radiation-sensitive element according to claim 15, wherein X^1, X^2 and X^3 are hexamethylene.

17 (New). The radiation-sensitive element according to claim 14 , wherein oligomer B is a phophazene represented by formula (IIa).

18 (New). The radiation-sensitive element according to claim 14 , wherein oligomer A is the reaction product of hexamethylene diisocyanate biuret and at least one acrylate of a multi-valent alcohol comprising at least one hydroxyl group, and oligomer B is represented by formula (IIa) wherein each

B^1, B^2, B^3, B^4, B^5 and B^6 are

$$-CH_2-CH_2-O-\overset{\overset{O}{\|}}{C}-C(CH_3)=CH_2.$$

19 (New). The radiation-sensitive element according to claim 14, wherein an oxygen-impermeable overcoat is provided on top of the radiation-sensitive coating.

20 (New). The radiation-senstive element according to claim 14, wherein the substrate is an aluminum foil or plate that has optionally been subjected to at least one pretreatment comprising roughening, anodizing or applying a hydrophilizing layer.

21 (New). A process for the production of an imaged element comprising

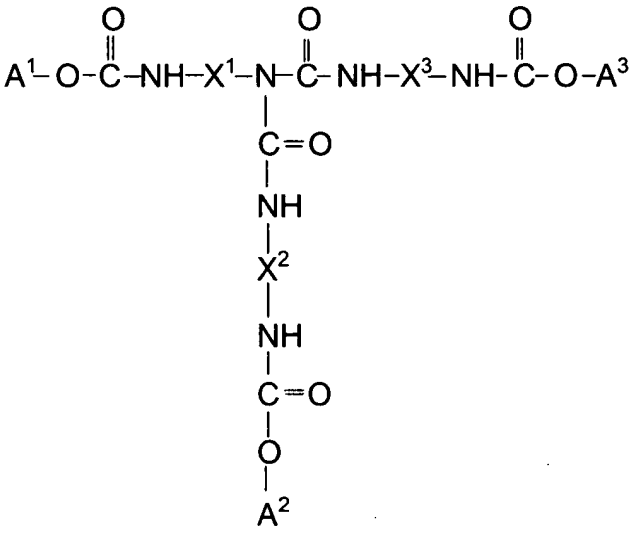
(a) providing a radiation-sensitive element

(1) an optionally pretreated substrate and

(2) a radiation-sensitive coating comprising

(i) at least one photoinitiator or sensitizer, which is capable of absorbing radiation of a wavelength in the range of 250 to 1,200 nm;

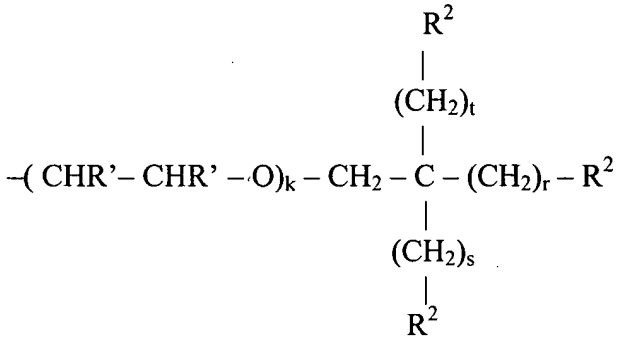
(ii) at least one oligomer A of formula (I)



(I)

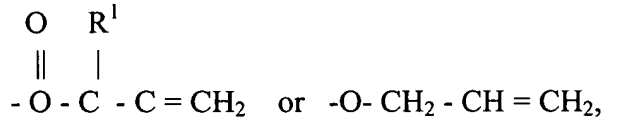
wherein X^1, X^2 and X^3 are independently C_2 – C_{18} alkanediyl or C_6 – C_{20} arylene,
A^1, A^2 and A^3 are independently

$-(CHR'-CHR'-O)_k-CH_2-CH=CH_2$ or a fragment represented by formula Ia



(Ia)

wherein k is an integer from 0 to 10, each R' is independently a hydrogen atom or CH_3, each R^2 is independently a hydrogen atom,

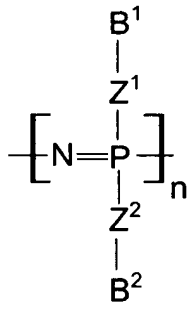


R^1 is a hydrogen atom or $C_1 - C_{12}$ alkyl and

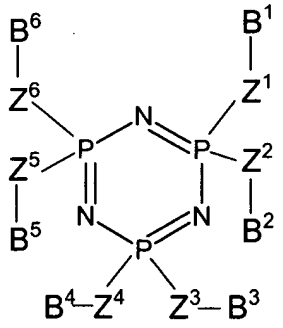
r, s and t independently are 0 or 1,

with the proviso that in each fragment A^1, A^2 and A^3 at least one R^2 is not a hydrogen atom if A^1, A^2 and A^3 are all fragments represented by formula (Ia), and

(iii) at least one oligomer B, which is a phosphazene represented by formulas (II) or (IIa):

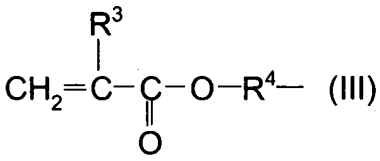


(II)



(IIa)

wherein Z^1, Z^2, Z^3, Z^4, Z^5 and Z^6 are independently –O– or –NR–, R is a hydrogen atom or $C_1 - C_{12}$ alkyl, n is greater than 3 and B^1, B^2, B^3, B^4, B^5 and B^6 are fragments represented by formulas (III) – (VIII)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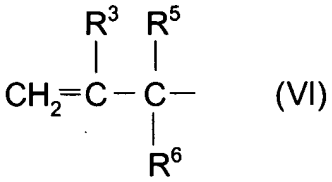
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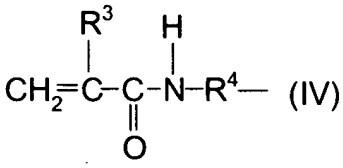
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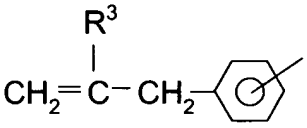
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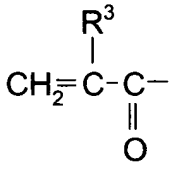
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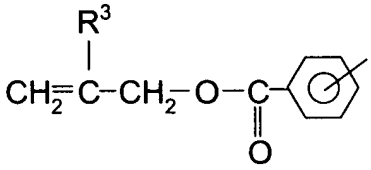

(VIII)

wherein R^3 is a hydrogen atom or $C_1 - C_{12}$ alkyl, R^4 is $C_2 - C_{12}$ alkanediyl and R^5 and R^6 are independently a hydrogen atom or $C_1 - C_{12}$ alkyl;

(b) image-wise irradiation of the radiation-sensitive element with radiation of a wavelength adjusted to the absorber contained in the radiation-sensitive coating of the element;

(c) optionally heating the image-wise irradiated element;

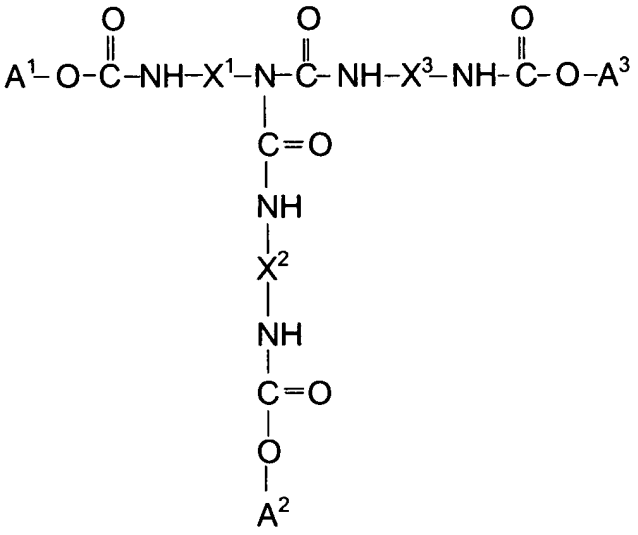
(d) removing the non-irradiated areas with an aqueous alkaline developer to provide the imaged element; and

(e) optionally heating the imaged element obtained in step (d) or subjecting it to overall exposure or both.

22 (New). A radiation-sensitive composition comprising

(i) at least one photoinitiator or sensitizer, which is capable of absorbing radiation of a wavelength in the range of 250 to 1,200 nm;

(ii) at least one oligomer A of formula (I)

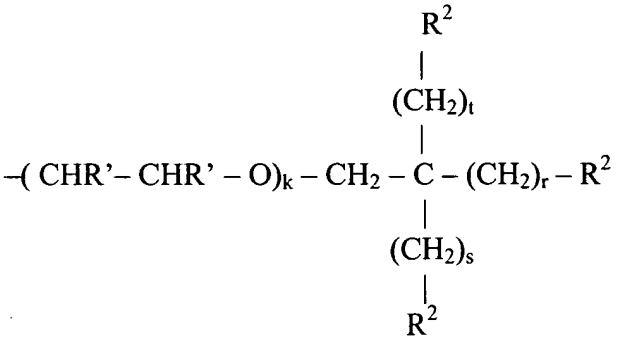


(I)

wherein X^1, X^2 and X^3 are independently $C_2 - C_{18}$ alkanediyl or $C_6 - C_{20}$ arylene,

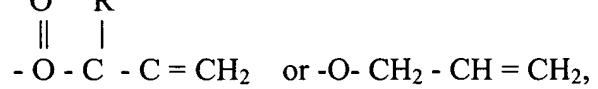
A^1, A^2 and A^3 are independently

$-(CHR'- CHR' - O)_k - CH_2 - CH = CH_2$ or a fragment represented by formula Ia



(Ia)

wherein k is an integer from 0 to 10, each R' is independently a hydrogen atom or CH_3, each R^2 is independently a hydrogen atom,



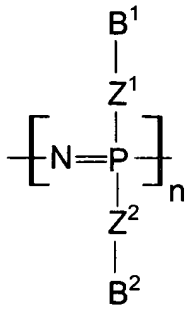
or -O- CH_2 - CH = CH_2,

R^1 is a hydrogen atom or $C_1 - C_{12}$ alkyl and

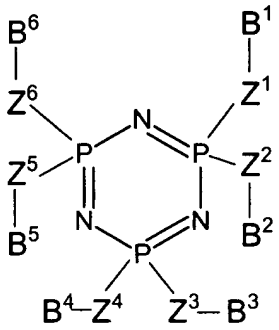
r, s and t independently are 0 or 1,

with the proviso that in each fragment A^1, A^2 and A^3 at least one R^2 is not a hydrogen atom if A^1, A^2 and A^3 are all fragments represented by formula (Ia), and

(iii) at least one oligomer B, which is a phosphazene represented by formulas (II) or (IIa):

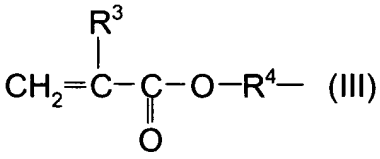


(II)

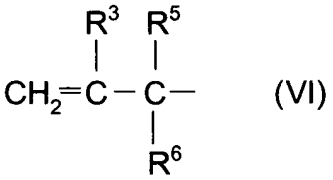


(IIa)

wherein Z^1, Z^2, Z^3, Z^4, Z^5 and Z^6 are independently –O– or –NR–, R is a hydrogen atom or $C_1 - C_{12}$ alkyl, n is greater than 3 and B^1, B^2, B^3, B^4, B^5 and B^6 are fragments represented by formulas (III) – (VIII)



(III)



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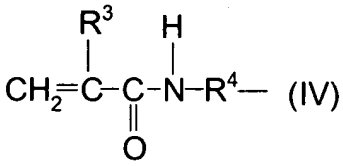

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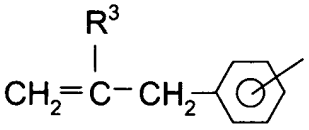

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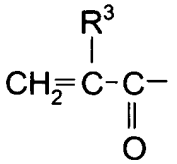

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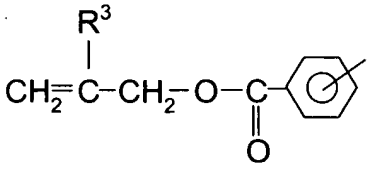


(VIII)

wherein R^3 is a hydrogen atom or $C_1 - C_{12}$ alkyl, R^4 is $C_1 - C_{12}$ alkanediyl and R^5 and R^6 are independently a hydrogen atom or $C_1 - C_{12}$ alkyl; and

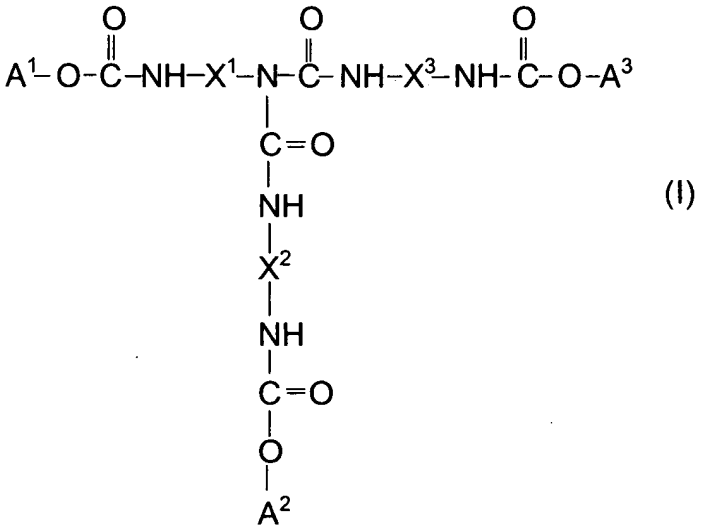
(iv) a solvent or solvent mixture; and

(v) optionally at least one additive comprising coinitiators which form free radicals after the excitation of the photoinitiator or sensitizer with radiation of a wavelength of 250 to 1,200 nm, binders, thermopolymerization inhibitors, dyes, plasticizers, chain transfer agents, leuco dyes, inorganic fillers or surfactants.

23 (New). A process for the production of a radiation-sensitive element comprising the steps of:

(a) providing an optionally pretreated substrate;
(b) applying a radiation-sensitive composition comprising:
(1) at least one photoinitiator and sensitizer, which is capable of absorbing radiation of a wavelength in the range of 250 to 1,200 nm;

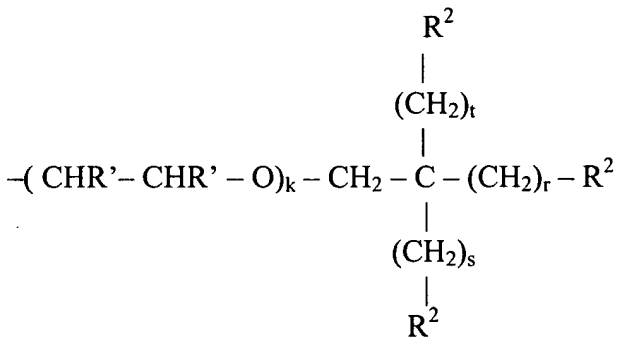
(2) at least one oligomer A of formula (I)



(I)

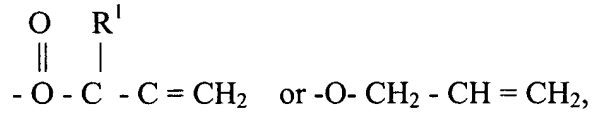
wherein X^1, X^2 and X^3 are independently $C_2 - C_{18}$ alkanediyl or $C_6 - C_{20}$ arylene,
A^1, A^2 and A^3 are independently

$-(CHR'- CHR' - O)_k - CH_2 - CH = CH_2$ or a fragment represented by formula Ia



(Ia)

wherein k is an integer from 0 to 10, each R' is independently a hydrogen atom or CH_3, each R^2 is independently a hydrogen atom,

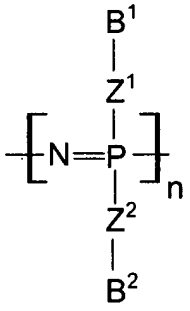


R^1 is a hydrogen atom or $C_1 - C_{12}$ alkyl and

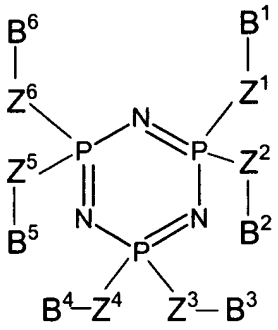
r, s and t independently are 0 or 1,

with the proviso that in each fragment A^1, A^2 and A^3 at least one R^2 is not a hydrogen atom if A^1, A^2 and A^3 are all fragments represented by formula (Ia), and

(3) at least one oligomer B, which is a phosphazene represented by formulas (II) or (IIa):

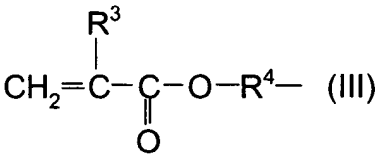


(II)



(IIa)

wherein Z^1, Z^2, Z^3, Z^4, Z^5 and Z^6 are independently –O– or –NR–, R is a hydrogen atom or $C_1 - C_{12}$ alkyl, n is greater than 3 and B^1, B^2, B^3, B^4, B^5 and B^6 are represented by formulas (III) – (VIII)



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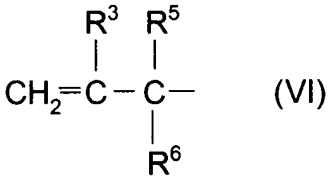

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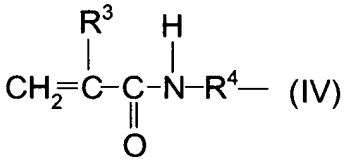

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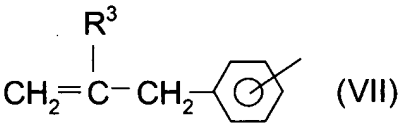
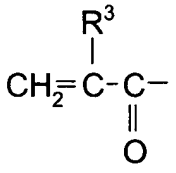
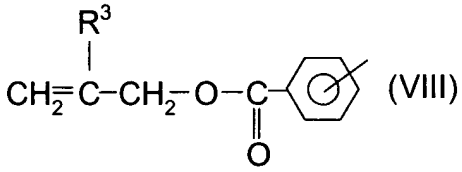


(VII)



(V)



(VIII)

wherein R^3 is a hydrogen atom or $C_1 - C_{12}$ alkyl, R^4 is $C_1 - C_{12}$ alkanediyl and R^5 and R^6 are independently a hydrogen atom or $C_1 - C_{12}$ alkyl; and

(4) a solvent or solvent mixture;

(c) drying; and

(d) optionally applying an oxygen-impermeable overcoat and drying.